Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

(Currently Amended) A semiconductor device characterized in device,
 comprising:

a semiconductor chip having a main surface and a sidewall;

a wiring layer formed on a-the main surface of a-the semiconductor chip; and a conductive layer for interlayer connections that is connected to the wiring layer and formed in a-the side wall of the semiconductor chip.

(Currently Amended) A semiconductor device characterized in device,
 comprising:

a semiconductor chip having a main surface;

electrode pads formed on a-the main surface of a-the semiconductor chip;

grooves formed in a section of the semiconductor chip that traverses in a
thickness direction of the semiconductor chip;

conductive layers filled in the grooves; and wiring layers that connect the electrode pads and the conductive layers.

3. (Currently Amended) A semiconductor module characterized in module, comprising:

semiconductor chips stacked in layers;

conductive layers that are formed in side walls of the respective semiconductor chips for providing to provide interlayer connections among the semiconductor chips; and

wiring layers that are formed on main surfaces of the respective semiconductor chips and connected to the conductive layers.

4. (Currently Amended) A semiconductor module characterized in module, comprising:

semiconductor chips stacked in layers;

electrode pads formed on main surfaces of the respective semiconductor chips;
grooves that are formed in sections of the respective semiconductor chips that
traverse in a thickness direction of the semiconductor chips;

conductive layers filled in the grooves for providing to provide interlayer connections among the semiconductor chips; and

wiring layers that connect the electrode pads and the conductive layers, respectively.

5. (Currently Amended) A semiconductor module characterized in module, comprising:

semiconductor chips stacked in layers;

electrode pads formed on main surfaces of the respective semiconductor chips;

grooves that are formed in sections of the respective semiconductor chips that
traverse in a thickness direction of the semiconductor chips;

wiring layers that connect the electrode pads and the conductive layers;

pin-like terminals that are embedded in the grooves and disposed in a stacking direction of the semiconductor chips;

an interposer substrate with the pin-like terminals standing thereon; and conductive layers filled in the grooves with the pin-like terminals therein.

6. (Currently Amended) A<u>The</u> semiconductor module according to claim 3, the semiconductor chips are being stacked in layers through dielectric resin.

7. (Currently Amended) A semiconductor module characterized in module, comprising:

an interposer substrate having a wiring layer formed on a main surface thereof;
a semiconductor chip that is-connected to the wiring layer and mounted on the interposer substrate;

grooves formed in a side wall of the interposer substrate that traverses in a thickness direction of the interposer substrate; and conductive layers filled in the grooves.

8. (Currently Amended) A semiconductor module characterized in module, comprising:

interposer substrates stacked in layers;

wiring layers formed on main surfaces of the interposer substrates;

semiconductor chips that are connected to the wiring layers and mounted on the interposer substrates;

grooves formed in side walls of the interposer substrates that traverse in a thickness direction of the interposer substrates;

conductive layers filled in the grooves for providing to provide interlayer connections among the interposer substrates; and

recessed sections formed in back surfaces of the interposer substrates for storing to store the semiconductor chips.

9. (Currently Amended) A semiconductor module characterized in module, comprising:

an intermediate substrate having an opening section formed therein; interposer substrates stacked in layers through the intermediate substrate; wiring layers formed on main surfaces of the interposer substrates;

semiconductor chips that are connected to the wiring layers and mounted on the interposer substrates;

first grooves formed in side walls of the interposer substrates that traverse in a thickness direction of the interposer substrates;

second grooves formed in a side wall of the intermediate substrate that traverses in a thickness direction of the intermediate substrate; and

conductive layers filled in the first grooves and the second grooves for providing to provide interlayer connections among the interposer substrates through the intermediate substrate.

10. (Currently Amended) An electronic device characterized in device, comprising:

semiconductor chips stacked in layers;

electrode pads formed on main surfaces of the respective semiconductor chips;

grooves that are formed in sections of the respective semiconductor chips that
traverse in a thickness direction of the semiconductor chips;

conductive layers filled in the grooves for providing to provide interlayer connections among the semiconductor chips;

wiring layers that connect the electrode pads and the conductive layers, respectively; and

an electronic component that is connected to the semiconductor chips through the conductive layers.

11. (Currently Amended) An electronic device characterized in device, comprising:

semiconductor chips stacked in layers;

electrode pads formed on main surfaces of the respective semiconductor chips;

grooves that are formed in sections of the respective semiconductor chips that traverse in a thickness direction of the semiconductor chips;

wiring layers that connect the electrode pads and the conductive layers, respectively;

pin-like terminals that are inserted in the grooves and disposed in a stacking direction of the semiconductor chips;

an interposer substrate with the pin-like terminals standing thereon;

conductive layers filled in the grooves with the pin-like terminals therein; and

an electronic component that is connected to the semiconductor chips through
the conductive layers.

12. (Currently Amended) An electronic device characterized in device, comprising:

interposer substrates stacked in layers;

wiring layers formed on main surfaces of the interposer substrates;

semiconductor chips that are connected to the wiring layers and mounted on the interposer substrates;

grooves formed in side walls of the interposer substrates that traverse in a thickness direction of the interposer substrates;

conductive layers filled in the grooves for providing to provide interlayer connections among the interposer substrates;

recessed sections formed in back surfaces of the interposer substrates for storing to store the semiconductor chips; and

an electronic component that is connected to the semiconductor chips through the conductive layers.

13. (Currently Amended) An electronic device characterized in device, comprising:

an intermediate substrate having an opening section formed therein;
interposer substrates stacked in layers through the intermediate substrate;
wiring layers formed on main surfaces of the interposer substrates;
semiconductor chips that are connected to the wiring layers and mounted on the interposer substrates;

first grooves formed in side walls of the interposer substrates that traverse in a thickness direction of the interposer substrates;

second grooves formed in a side wall of the intermediate substrate that traverses in a thickness direction of the intermediate substrate;

conductive layers filled in the first grooves and the second grooves for providing to provide interlayer connections among the interposer substrates through the intermediate substrate; and

an electronic component that is connected to the semiconductor chips through the conductive layers.

14. (Currently Amended) A method for of manufacturing a semiconductor device, characterized in comprising:

a step of forming through holes on cutting lines of a semiconductor wafer; a step of cutting the semiconductor wafer along the cutting lines into chips;

a step of filling conductive layers in the through holes divided by the cutting step.cutting.

and

15. (Currently Amended) A method for of manufacturing a semiconductor device, characterized in comprising:

a step of forming trench sections on cutting lines of a semiconductor wafer having wiring layers formed thereon;

a step of forming dielectric films within the trench sections;

a step of forming an under barrier metal layer that covers the dielectric films and is connected to the wiring layers;

a step of thinning a back surface of the semiconductor wafer to thereby make the trench sections penetrate to form through holes along the cutting lines;

a step of cutting the semiconductor wafer along the cutting lines into chips; and

a step of filling conductive layers in the through holes that are divided by the cutting-step.

16. (Currently Amended) A method for of manufacturing a semiconductor module, characterized in comprising:

a step of forming conductive layers on side walls of a semiconductor chip; and a step of providing interlayer connections through the conductive layers formed on the side walls of the semiconductor chip.

17. (Currently Amended) A method for of manufacturing a semiconductor module, eharacterized in comprising:

a step of forming through holes on cutting lines of a semiconductor wafer;

a step of cutting the semiconductor wafer along the cutting lines into chips;

a step of stacking the semiconductor chips formed by the cutting step; cutting;

and

a step of filling conductive layers in the through holes cut by the eutting step.cutting.

18. (Currently Amended) A method for of manufacturing a semiconductor module, eharacterized in comprising:

a step of forming through electrodes on cutting lines of a semiconductor wafer;

a step of cutting the semiconductor wafer along the cutting lines into chips;

a step of providing interlayer connections among the semiconductor chips formed by the cutting step-via the through electrodes that are cut by the cutting step-cutting.

19. (Currently Amended) A method for of manufacturing a semiconductor module, characterized in comprising:

and

and

a step of forming trench sections on cutting lines of a semiconductor wafer having wiring layers formed thereon;

a step of forming dielectric films within the trench sections;

a step of forming an under barrier metal layer that covers the dielectric films and is connected to the wiring layers;

a step of thinning a back surface of the semiconductor wafer to thereby make the trench sections penetrate to form through holes along the cutting lines;

a step of cutting the semiconductor wafer along the cutting lines into chips;
a step of stacking the semiconductor chips formed by the cutting step; cutting;

a step of filling conductive layers in the through holes that are divided by the cutting step.

20. (Currently Amended) A method for of manufacturing a semiconductor module, characterized in comprising:

a step of forming through holes on cutting lines of a semiconductor wafer;

a step of cutting the semiconductor wafer along the cutting lines into chips;

a step of stacking the semiconductor chips on a interposer substrate having

pin-like terminals standing thereon in a manner that the pin-like terminals are inserted in the through holes divided by the cutting step; cutting; and

a step of filling conductive layers in the through holes that are cut.

21. (Currently Amended) A method for of manufacturing a semiconductor module, characterized in comprising:

a step of mounting semiconductor chips on interposer substrates having grooves formed in side walls thereof and recessed sections formed in back surfaces thereof;

a step of stacking the interposer substrates having the semiconductor chips mounted thereon in layers layers, such that each of the semiconductor chips is stored in each of the recessed sections of an upper layer of the stacked interposer substrates; and

a step of filling conductive layers in the grooves of the interposer substrates to provide interlayer connections.

22. (Currently Amended) A method for of manufacturing a semiconductor module, characterized in comprising:

a step of mounting semiconductor chips on interposer substrates having grooves formed in side surfaces thereof;

a step of stacking the interposer substrates having the semiconductor chips mounted thereon through intermediate substrates having opening sections formed in main surfaces thereof and grooves formed in side walls thereof; and

a step of filling conductive layers in the grooves of the interposer substrates and the intermediate substrates to provide interlayer connections.

Amendments to the Drawings:

The attached replacement drawing sheets make changes to Figs. 14(a)-14(d) and 15(a)-15(d) and replace the original sheets with Figs. 14(a)-14(d) and 15(a)-15(d).

Attachment: Replacement Sheets